

CLAIMS

1. A radiation sensitive resin composition, comprising (1),
(a) an alkali-soluble resin having no epoxy group and (b)
5 a 1,2-quinonediazide compound, and (2) being for forming an
insulating film for an organic EL display element.

2. The composition of claim 1, wherein the alkali-soluble
resin (a) is a novolak resin having no epoxy group.
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3. The composition of claim 1, wherein the alkali-soluble
resin (a) is a copolymer having no epoxy group of (1a) at
least one unsaturated monomer selected from the group
consisting of an unsaturated carboxylic acid, unsaturated
15 carboxylic anhydride and phenolic hydroxyl group-containing
unsaturated monomer, and (2a) an olefinic unsaturated monomer
other than the above unsaturated monomer (1a).

4. The composition of claim 1 which further comprises (c)
20 a basic nitrogen-containing compound.

5. The composition of claim 1 which further comprises (d)
at least one compound selected from the group consisting of
a melamine compound and an epoxy compound.
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6. A radiation sensitive resin composition, comprising (1),
(a') an alkali-soluble resin having an epoxy group and (b)
a 1,2-quinonediazide compound, and (2) being for forming an
insulating film for an organic EL display element.
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7. The composition of claim 1, wherein the alkali-soluble
resin (a') having an epoxy group is a copolymer having an
epoxy group of (1a') an unsaturated monomer having an epoxy
group, (2a') at least one unsaturated monomer selected from

the group consisting of an unsaturated carboxylic acid, unsaturated carboxylic anhydride and phenolic hydroxyl group-containing unsaturated monomer, and (3a') an olefinic unsaturated monomer other than the above unsaturated monomers 5 (1a') and (2a').

8. An insulating film for an organic EL display element, formed from the radiation sensitive resin composition of claim 1 or 6.

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9. Use of the radiation sensitive resin composition of claim 1 or 6 for the production of an insulating film for an organic EL display element.

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10. An organic EL display element having an insulating film formed from the radiation sensitive resin composition of claim 1 or 6.